PROJECTED RANGE STATISTICS

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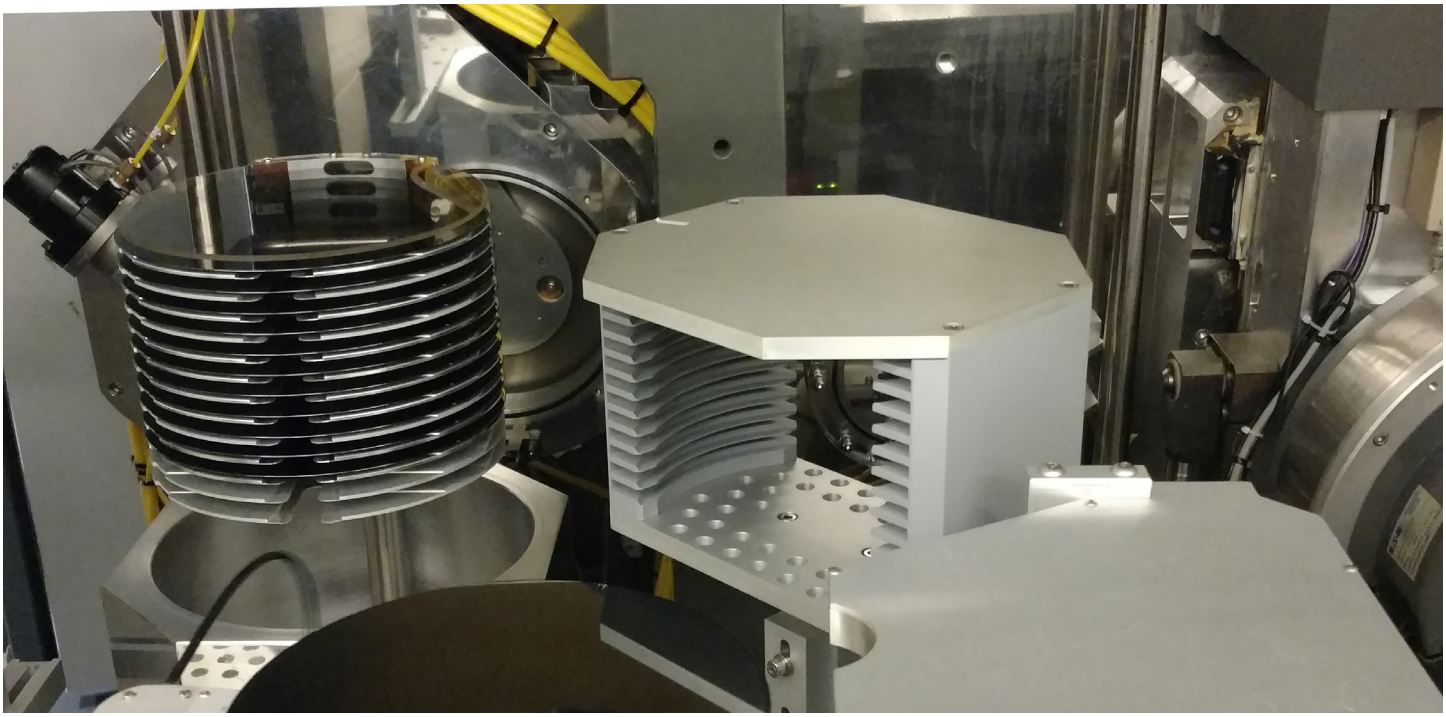
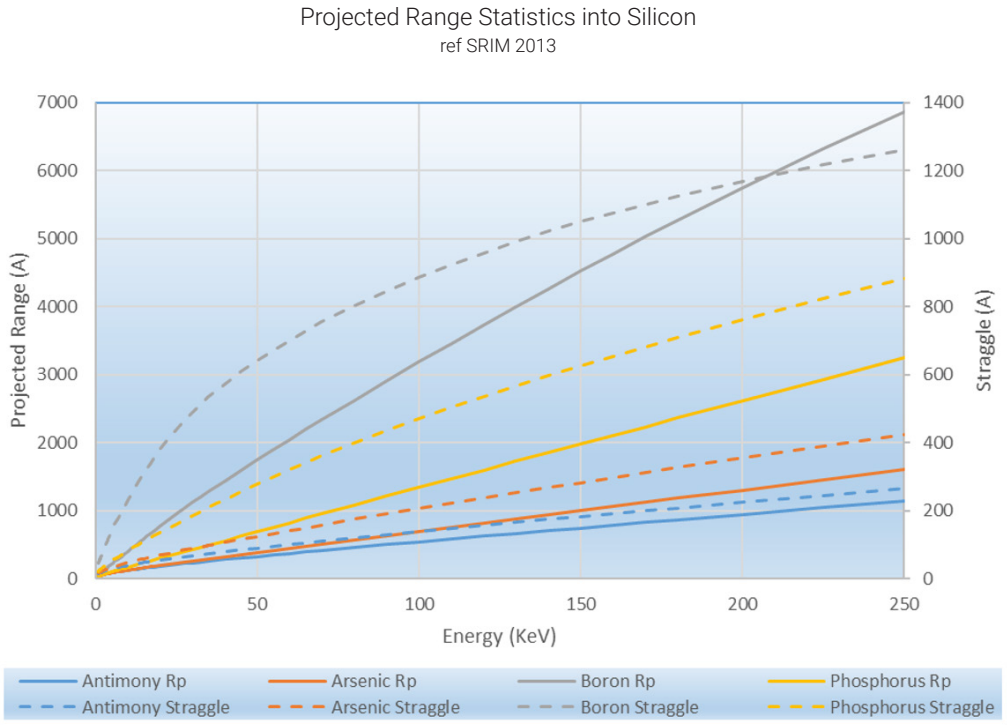
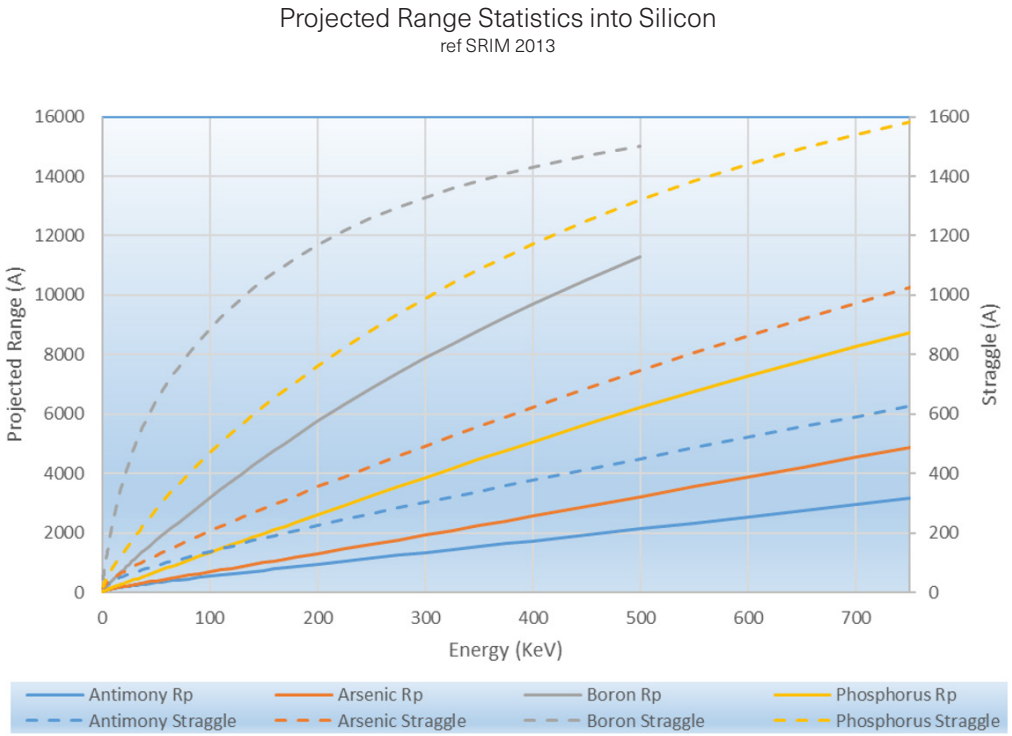


- The following graphs are based on tables generated by SRIM 2013
- SRIM is a software package originally written at IBM Research under the direction of J. F. Ziegler and J. P. Biersack
- It is currently available at no cost for noncommercial use at www.SRIM.org
- The graphs are provided for use by any and all ion implant users
- The graphs provide Projected Range (Rp) and Straggle (ΔRp) for
  - Antimony
  - Arsenic
  - Boron
  - Phosphorus
- There are 4 sets of graphs for the following implant target materials
  - Silicon
  - Silicon Dioxide
  - Silicon Nitride
  - Resist (AZ 111)
- Each set of graphs consist of 2, one for singly charge ions and one for multiply charge ions
- In addition, there is a set of graphs recommending a minimum resist thickness
- The recommendations are based on Rp + 5 * ΔRp.
- Thicker resist may be needed for high doses that cause resist shrinkage

COHERENT

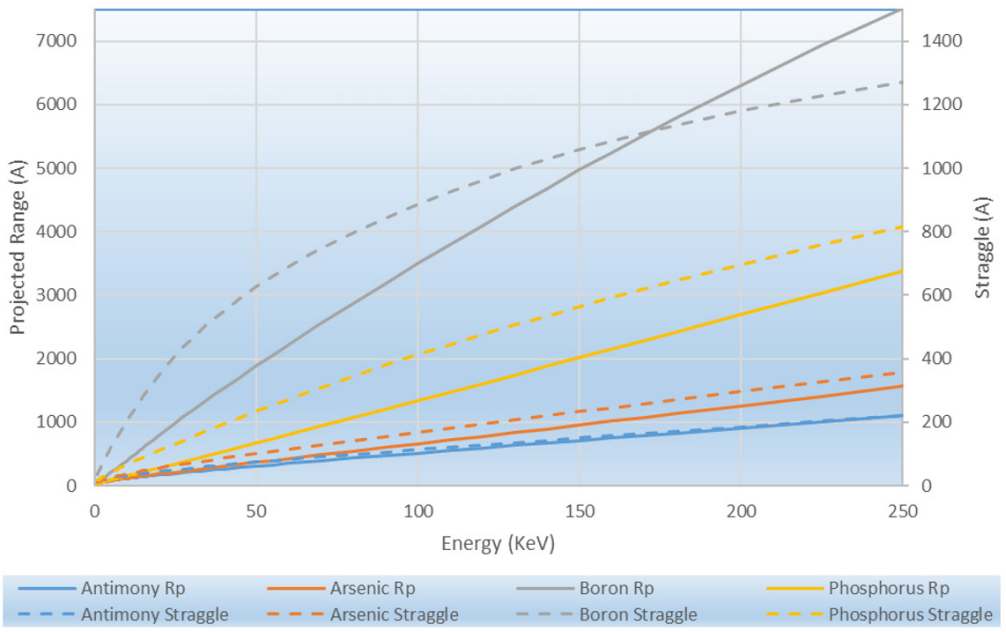


- Based on SRIM 2013 generated tables



- Based on SRIM 2013 generated tables

Projected Range Statistics into Oxide
ref SRIM 2013



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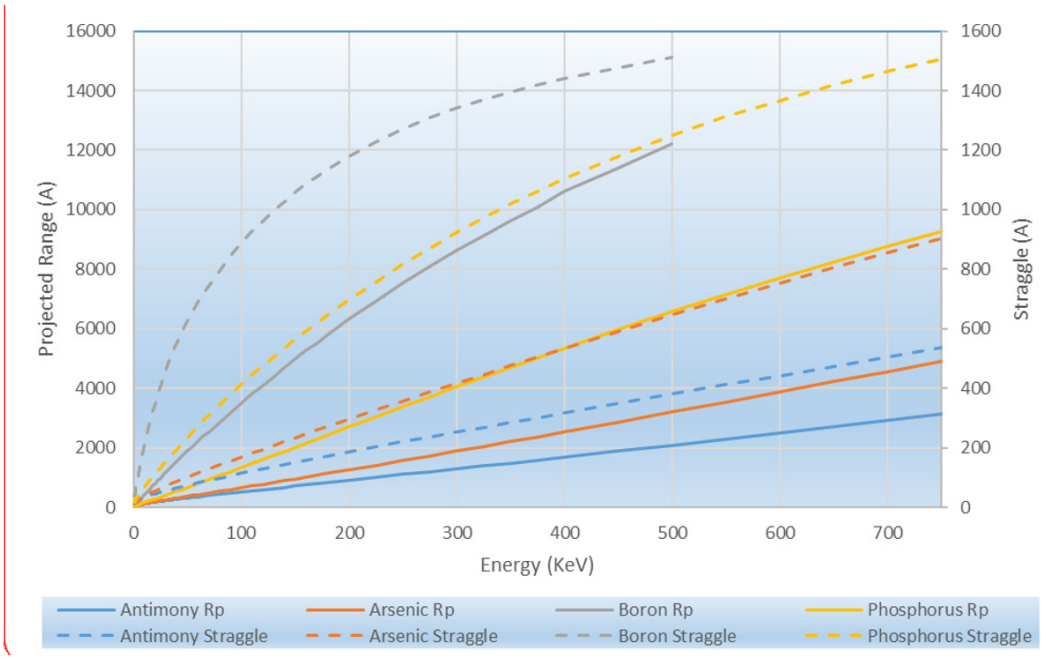
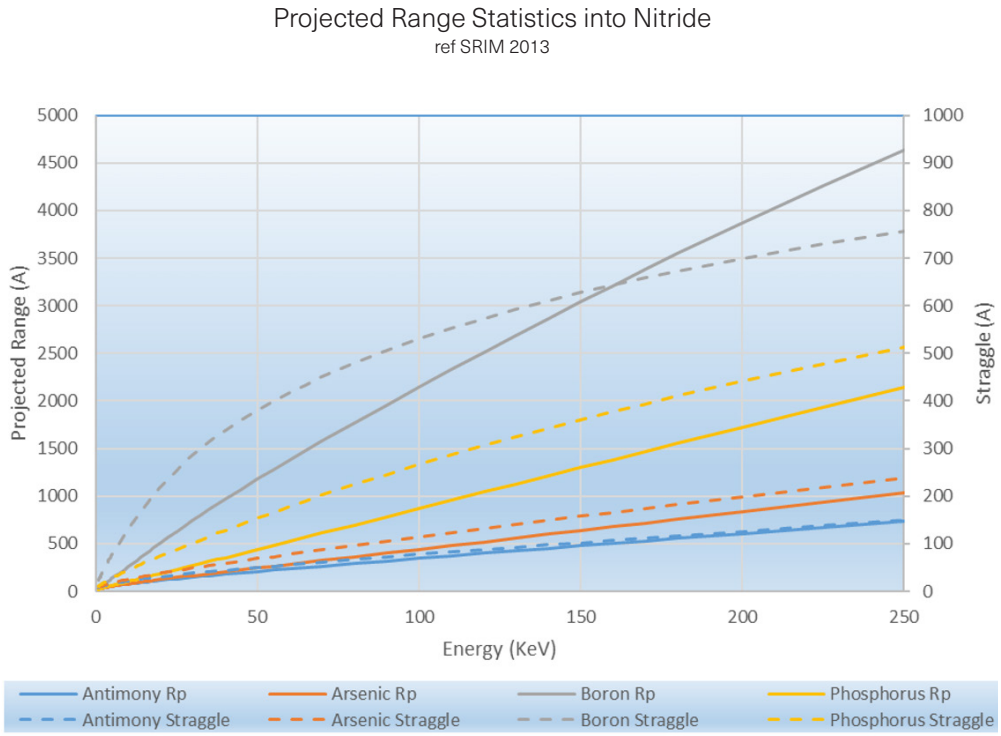
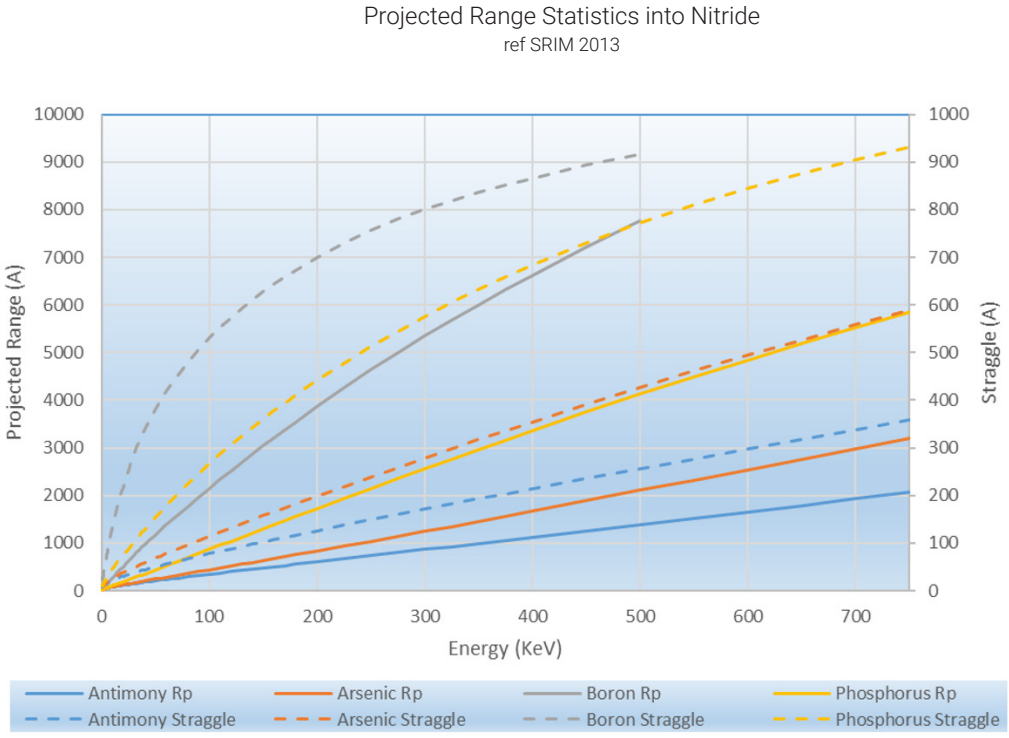


- Based on SRIM 2013 generated tables

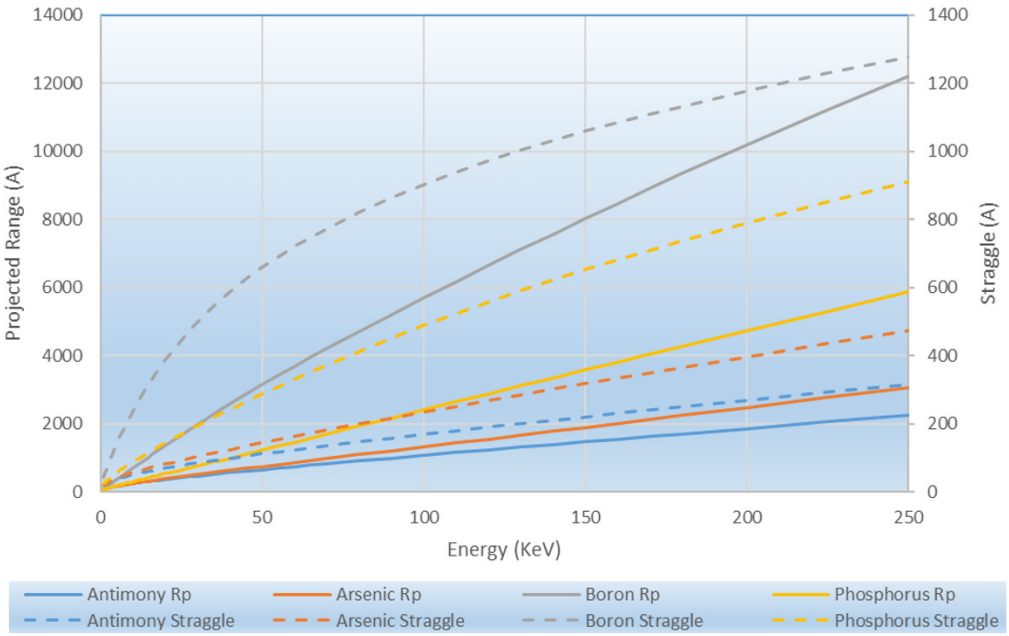


- Based on SRIM 2013 generated tables



- Based on SRIM 2013 generated tables

Projected Range Statistics into AZ-111 Resist
ref SRIM 2013



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Projected Range Statistics into AZ-111 Resist
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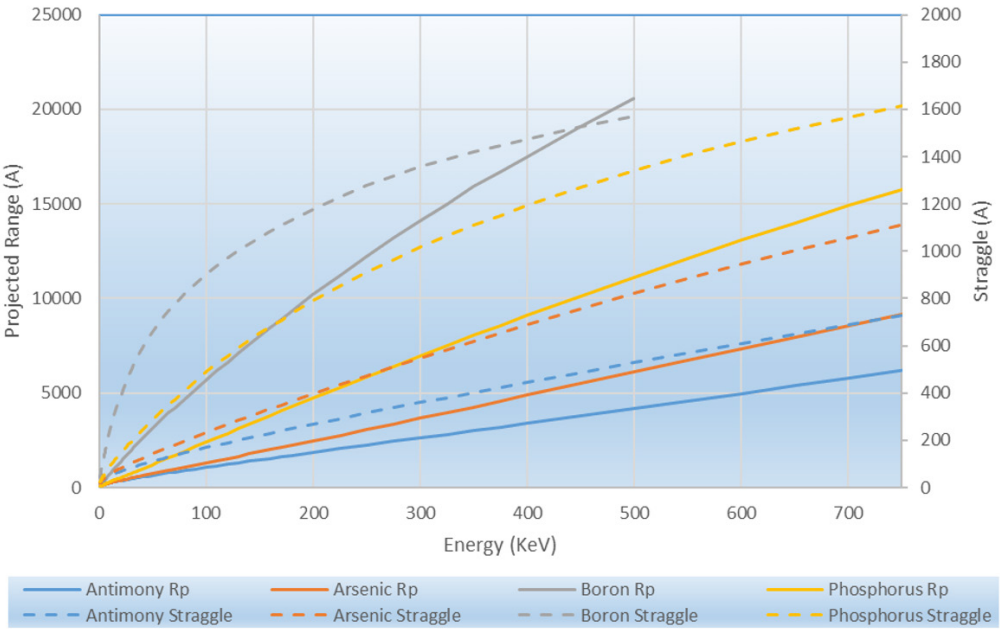

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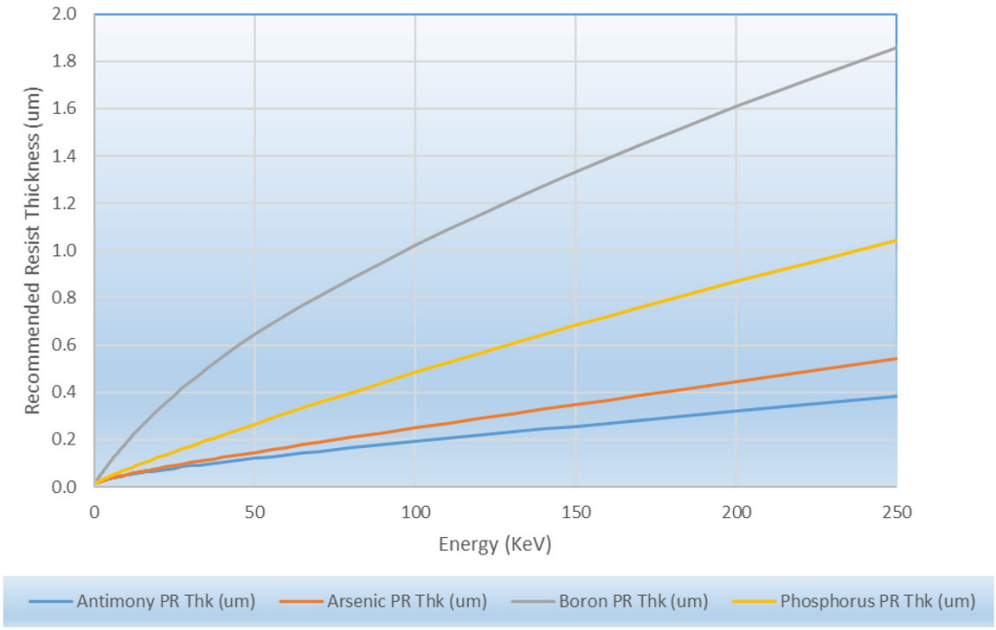
Projected Range + 5 * Statistics -- Recommended Resist Thickness
ref SRIM 2013



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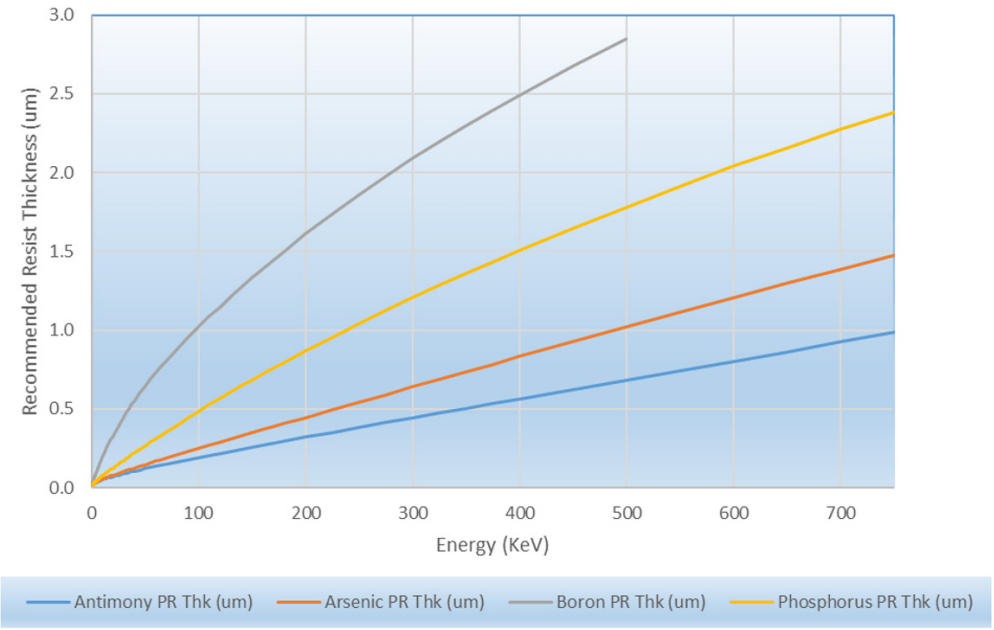

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